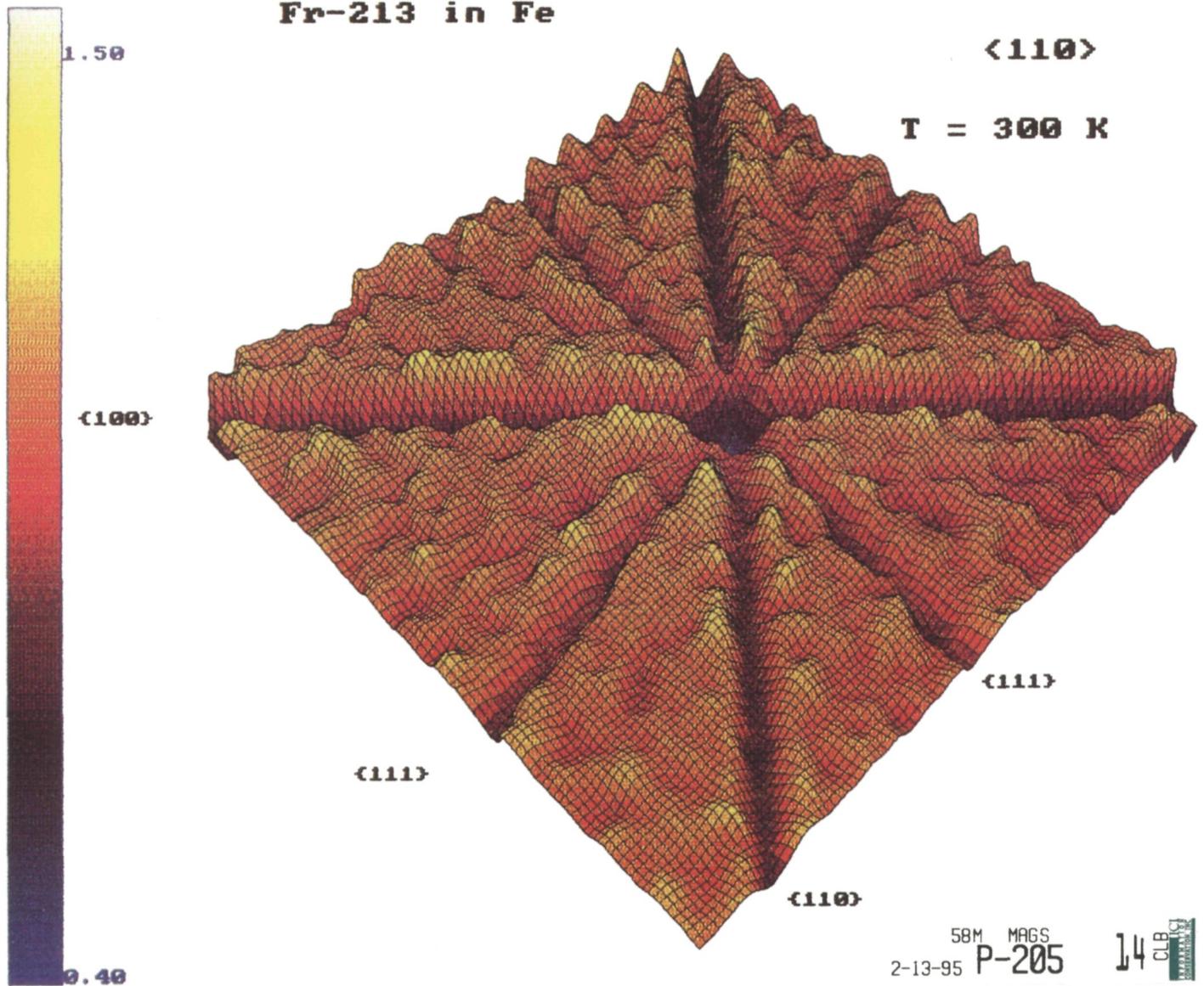




## Quantitative Analysis of Thin Films

### Part II

Fr-213 in Fe



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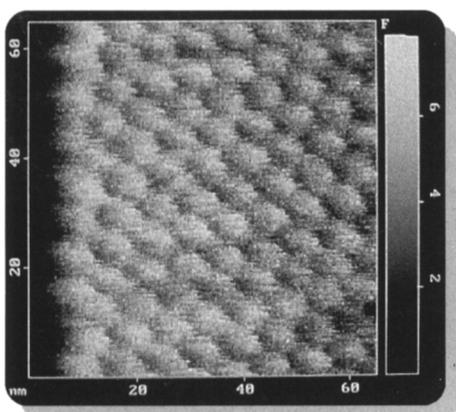


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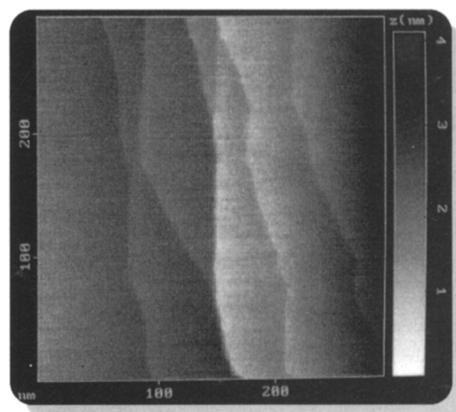
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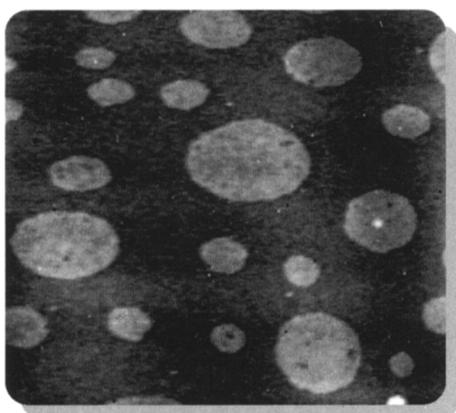
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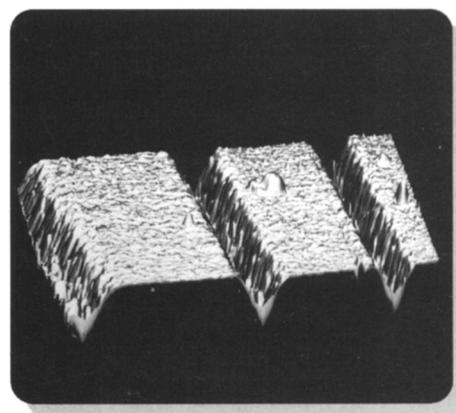
Atomic resolution on mica in UHV



Mono-atomic steps on Si (111) in UHV



2.7  $\mu\text{m}$  large area scan with Langmuir Blodgett film, step height 2.5 nm



Magneto optical disc, scan range 3.8  $\mu\text{m}$

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# MRS BULLETIN

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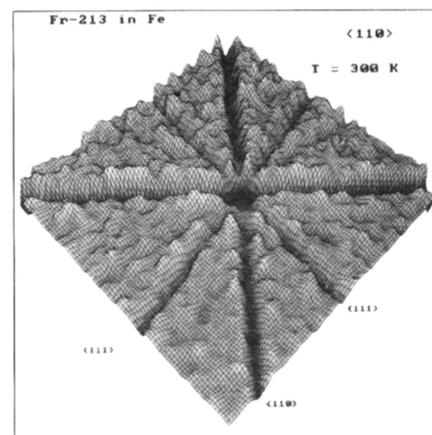
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**ON THE COVER:** The cover shows the blocking pattern formed by  $\alpha$ -particles emitted from radioactive francium atoms—the biggest atom in nature!—implanted in an iron single crystal to an average depth of only 100 Å. For more about this topic, see “Quantitative Rutherford Backscattering from Thin Films” by W.K. Chu and G. Langouche, starting on page 32.

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University College London  
Dept. of Electronic and  
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Torrington Place  
London WC1 E7 JE  
United Kingdom  
71-387-7050 ext. 3956 or 7304

### Editorial and Advertising Offices

9800 McKnight Road  
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Telephone (412)-367-3036  
Fax (412) 367-4373

### MRS Office of Public Affairs

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